



AMAT Docket No.: 005040/TCG/PMD/LE
BSTZ Docket No.: 4887P522

JUN -8 2001

Patent

#2/4
12/9/02
N/A

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE
TC 2800 MAIL ROOM

In re Application of:

Curry et al.

Application No.: 09/828,067

Filed: April 6, 2001

For: A WAFER PROCESSING APPARATUS
HAVING A CHAMBER WITH AN UPPER
WALL HAVING GAS SUPPLY OPENINGS
FORMED THEREIN WHICH PROMOTE
MORE EVEN PROCESSING OF A WAFER

Examiner: Sarkar, A.

Art Group: 2813

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Name of Person Mailing Correspondence
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Commissioner of Patents
Washington, DC 20231-9998

PRELIMINARY AMENDMENT

Sir:

Prior to the examination of the above-identified application, please amend the
application as follows and consider the following remarks:

IN THE CLAIMS

The following claims are pending in the Patent Application:

21. (New) A wafer processing apparatus comprising:
- a processing chamber defined by a lower wall, an upper wall and side walls
extending from the lower wall to the upper wall, a wafer supply opening being formed
in one of the walls for transferring a wafer into the chamber;

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